

Product Samples

ATP1010: Fused Silica/Quartz Circuit

Applied Thin-Film Products (ATP) is pleased to provide ceramic thin-film samples for your evaluation.

TaN/TiW/Au on Fused Silica/Quartz is used in applications that require a low dielectric constant material. This material has a 60/40 Optical polish with high dimensional accuracy.

Material Specifications

Fused Silica Quartz

Properties	Values
Chemical Composition	SiO ₂
Purity	100%
Color	Transparent
Nominal Density	60/40 g/cm ³ Optical
Surface Finish (Polished) CLA	0.2μ" (0.5nm)
Camber	0.002" (0.508μm)
Thickness	0.004–0.025" (0.100–0.635mm)
Thickness Tolerance (±)	0.0005" (12.7μm)
Coefficient of Thermal Expansion (CTE)	0.65 x 10 ⁻⁶ (25–1000°C)
Dielectric Constant (k)	3.826 @ 1 MHz
Dissipation Factor (Loss Tangent)	0.000015 @ 1 MHz
Hardness (Rockwell)	7 Mohs
Flexural Strength	25K (10 ⁻³) lbs/in ²
Compressive Strength	161 x 10 ³ M lbs/in ²
Grain Size	Amorphous

Material Specifications provided by Accumet Engineering Company

ATP1010, Material is 15 mil Fused Silica/Quartz
 TaN Resistors = 50 Ohms per Square
 TiW = 400–800 Ångström
 Au = 120μ" minimum
 Does not have indicator on circuit

Sample Provided



ATP offers build-to-print service for a wide range of materials and metalization schemes. ATP fabricates circuits on substrates from As-Fired Alumina to Beryllium Oxide to Fused Silica, even Silicon. Metalizations range from the standard TaN/TiW/Au to films including Nickel, Palladium, or Titanium.

At ATP, we constantly evolve our processing and material capabilities to reflect our customer's changing needs. If you have a circuit requirement that is out of the "normal" thin-film type, please contact ATP at 1.510.661.4287 or visit our website at www.thinfilm.com. ATP would enjoy discussing your application with you and working to develop a solution.